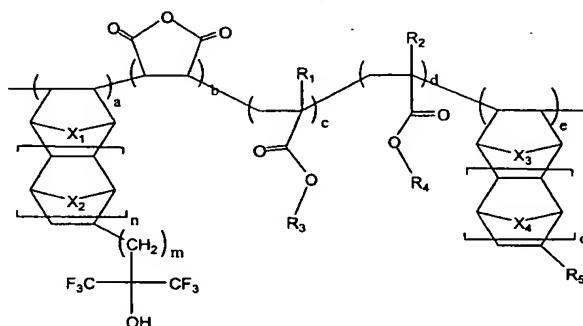


ABSTRACT OF THE DISCLOSURE

Photoresist polymers and photoresist compositions are disclosed. A photoresist polymer represented by Formula 1 and a photoresist composition containing the same have excellent etching resistance, thermal resistance and adhesive property, and high affinity to an developing solution, thereby improving LER (line edge roughness).

Formula 1



wherein

10 $X_1, X_2, X_3, R_1, R_2, R_3, R_4, R_5, m, n, o, a, b, c, d$ and e are as defined in the description.